Non-Perturbative Measurements ^{using} Minimum Photon Approaches

Perturbation Limits

- General physics of x-ray interactions (e.g. cross-sections)
- Perturbation limits of soft and hard matter
- Imaging resolution versus dose

Extracting maximum information from each photon

- Better algorithms
- Improved optics
- Advanced detectors

Integrated approaches to solving scientific problems

- X-ray measurements
- Theory and large scale simulation
- Other probes (e.g. TEM, optical spectroscopy)

Fundamental Questions in Materials Science

What materials are present?

Where are the materials located?

When do crucial transformations and processes occur?

Why does a material have its structure and properties?



Scattering Calculations: Cross-Sections versus



Note that the absorption cross-section is always much larger than the scattering cross-section

Scattering Cross Section



The strong scattering over all of angle space is why crystallographers often prefer to work at lower photon energy (i.e. the scattered intensity is spread out of a large angle space and the integrated intensities are much higher.

Scattering Cross Section



Scattering Calculations: Include Atomic Correlations



Polarization Switching in Ferroelectric Oxides

The ferroelectric polarity of a thin $PbTiO_3$ film can be switched by changing the boundary conditions through gas phase chemistry.



X-rays "improve" kinetics of chemical switching







Elapsed time (sec)

10 nm PTO/SRO/STO at 500C

- up to down switch is the "slow switch" (~2800 sec)
 → 0.23 to 2.4x10⁻⁵ Torr
- time delay in up to down switch ≈ time x-rays are off sample

Effect of x-rays on c lattice parameter (monodomain up)

- X-rays help compensate depolarizing field (larger *c* lattice parameter)
- In the up state (10 nm PTO/SRO/STO at 500C at pO₂=2.3 Torr)
 - fast response to x-rays



Effect of x-rays on c lattice parameter (monodomain down)

- X-rays help compensate depolarizing field (larger *c* lattice parameter)
- In the down state (10 nm PTO/SRO/STO at 500C at pO₂=2.4x10⁻⁵ Torr)
 - slower response to x-rays



Damage to Epitaxial PbTiO₃ Film During Ptychography

Main Bragg peak shows partial relaxation out-of-plane lattice parameter.

Also, stripe satellite peaks diminish in intensity and sharpness as PTO stripes become more disordered.

002 PTO peak from a 40-nm diameter spot illuminated repeatedly with 10 second exposures. After 200 sec of accumulated exposure, changes begin After 600 sec, we see Bragg peak relaxation and stripe disorder.



Stress and Strain are Key to Mesoscopic Behavior

- Stress and strain are important materials parameters available to manipulate properties and performance.
- Control and prediction of lattice responses is challenging since they depend on the complete environment and processing history.
- Measurement and visualization of lattice distortions is necessary to understand the structure and performance in mesoscale systems.
- Studies must be done *in operando* to avoid changing the device boundary conditions.

Example: SiGe stressor layers are used to locally modify band structure and improve silicon device performance.



3D Bragg ptychography has great potential for *in operando* studies

Difference between Tilt and Strain





Nanodiffraction from SiGe Device



Work by Martin Holt, Stephan Hruszkewycz, Conal Murray, Judson Holt, Debbie Paskiewicz and PHF



SiGe Device Strain and Deformation

Modeling almost exactly reproduces our BPP reconstruction.

Boundary element method (BEM) calculation shows that there should be both tilts and strain near the active channel.





Damage to Epitaxial SiGe on SOI



Black region is location of a ptychography spiral scan: 1000 pts, ~600nm diameter, 10 sec exposures, 40nm focused beam diameter, 13nm step size, 65% overlap.

Estimate of flux, 9×10⁸ in the focused spot

Scan shown taken with <1 sec exposures to assess damage, plotted as Bragg peak centroid along the 2θ direction

Position B, undisturbed



Position A, modified



Relaxed film peak Shifted to high-2θ



- Ga -> atomic liquid
- Si (111) monochromator
- Be lenses focus to 1.7 microns





- XPP hutch at LCLS
- High angle diffracted speckle recorded by CCD
- Samples:
 - Pd₄₀Ni₄₀P₂₀ -> heavy glass
 - B₂O₃ -> light glass
 - Ga -> atomic liquid
- Si (111) monochromator
- Be lenses focus to 1.7 microns



Is There a Useful Non-Perburbative Window?



Coherent Speckle







Poisson "Shot Noise"

Coherent Speckle







Poisson "Shot Noise"

Coherent Speckle







Poisson "Shot Noise"

 $\beta = 0$

Coherent Speckle



Poisson Shot Noise

$$\beta = 0$$

ate:
bixel

 β

"

77





Coherent Speckle







Poisson "Shot Noise"

High angle liquid scattering



Single pulse scattering patterns are very weak and need to be carefully analyzed in order to determine contrast.



The droplet algorithm

- Step 1: Identify regions of connectivity, i.e. droplets
 - Histogram of droplets by their total counts clearly separates photon events



F. Livet et al., Nucl. Instrum. Meth. A 451, 596 (2000).

Droplets accurately identify regions of correlated intensity.

Detector pixels



The droplet algorithm

- Step 1: Identify regions of connectivity, i.e. droplets
 - Histogram of droplets by their total counts clearly separates photon events
- Step 2: Fit each droplet by least squares to identify positions of photons
- Step 3: After photons were extracted, they were re-gridded onto the detector pixels.
 - Accurate determination of P(1) and P(2)

$$P(1) \approx \overline{k} - (1+\beta)\overline{k}^2$$
$$P(2) \approx \frac{(1+\beta)\overline{k}^2}{2} - \frac{(1+\beta)(1+2\beta)\overline{k}^3}{2}$$

Technique identifies the x,y coordinate of every photon.

Detector pixels



Measuring contrast from liquid Ga

Experimental considerations define maximum attainable contrast:

 $\boldsymbol{\beta}_{calc}(\boldsymbol{p},\boldsymbol{L},\boldsymbol{Q},\boldsymbol{t},\boldsymbol{\theta},\Delta\boldsymbol{E}/\boldsymbol{E},\boldsymbol{s}_{x},\boldsymbol{s}_{y})$

The experimental value $\beta_{Ga} = 0.276 \pm 0.004$ was determined from droplet fitting analysis, and matches the maximum attainable $\beta_{calc} = 0.307$ for this geometry



(Note the large range of incident pulse energies)

X-Ray Energy Deposition is Larger Than Focus

- Most of the x-ray energy is carried away by high energy electrons and fluorescent photons that have a range of many microns.
- Energy is deposited well outside a sub-micron focus.
- Sample perturbation doesn't scale like the inverse of the focal spot size.





Oscillatory Growth and Decomposition

- Near phase boundaries system can spontaneously oscillate
 - Inter-conversion between InN and liquid In
- AFM of quenched samples shows microstructure of distinct surface species







Real-time Observations of Chemical Waves during Oscillatory Growth and Decomposition of InN

Oscillatory Pattern Formation during MOCVD of InN on GaN

1. Expanding circular pattern

| Actual elapsed time: | 1 hour 25 min |
|-----------------------------------|-----------------------|
| Temperature: | 664°C |
| TMI flow rate: | 0.145 μmol/min |
| NH ₃ partial pressure: | 27 Torr |
| Total pressure: | 200 Torr |
| Sample size: | 15x15 mm ² |

Attacking the Problem on Multiple Fronts

Understanding complicated problems such as WBG synthesis and fabrication requires a variety of *in-situ* probes and computational techniques

In-situ X-ray Analysis



X-Ray Imaging of Defects





Theory & Modeling

First-principles Calculations

- Calculate the lowest energy configurations of NH₃, NH₂, NH, N, and H on a GaN and InN surface
- Create a phase diagram predicting the equilibrium coverage species for given conditions

(2x2) surface unit cell

- 4 H3 "hollow" sites
- 4 T1 "on top" Ga sites
- 4 T4 "on top" N sites
- 12 br "bridge" site

~10³ structures possible



"We" = Peter Zapol, Weronika Walkosz, and Xin Tan

Intermediate Chemical Species

- The local intermediate chemical species dictate growth behavior
- Different surfaces catalytically crack NH₃ differently and possibly change residence time of intermediate species
- If we can understand which intermediate species enable InN growth, then we can better stabilize and encourage its formation
- What are the intermediate nitrogen species?
 - First principle calculations
 - Additional *in-situ* probes



Phase Diagrams at Finite Temperatures

- Many possible structures depending on the chemical potential (μ)
- Surprisingly, some structures do not obey electron-counting rule
- Can we identify these structures experimentally?



W.Walkosz, P. Zapol and G. B. Stephenson, *Phys. Rev. B* 85, 033308 (2012)

CTR Analysis of Structures

- First Principle can be used to predict CTRs for each phase
- Can we see these changes with in-situ x-rays?
- Have not found unique solutions

log(l) [a.u.]





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Advanced x-ray techniques provide unique information by looking into and through complex materials and devices.

Coupled with theory and advanced computing capabilities, this information enables a detailed understanding of material processing technologies and device physics.

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Atomic Resolution, Ultrafast X-Ray Speckle from Liquids

Paul Fuoss, Stephan Hruszkewycz, Stephan Rosenkranz, Bernard Adams and Brian Stephenson, Argonne National Laboratory

Mark Sutton, McGill University

Karl Ludwig, Boston University

Aymeric Robert, Dave Fritz, Marcin Sikorski, Sooheyong Lee, Diling Zhu, Marco Cammarata and Henrik Lemke, SLAC National Accelerator Laboratory

Christian Gutt, Wojciech Roseker and Gerhard Grubel, Deutsches Elektronen-Synchrotron





Scattering Calculations: Cross-Section of a Copper



Scattering Considerations: Basic Equation

Now we'll develop the x-ray scattering in more detail because that strongly impacts experimental design. The basic scattering equation is:

$$d\sigma(\vec{Q}) = \left(\frac{e^4}{m^2 c^4}\right) \sum_{i=1}^{N_{atoms}} \sum_{j=1}^{N_{atoms}} f_i(\vec{Q}) f_j(\vec{Q}) e^{-\vec{Q} \cdot \vec{R}_{ij}} d\Omega$$

where

Q = the difference between the exit and incident wavevectors

 \overline{R}_{ij} = the vector connecting atoms i and j

 f_i = the atomic scattering factor of atom i